Supporting Information

Femtosecond laser regulatory focus ablation patterning of fluorescent film up to 1/10 the scale of the diffraction limit

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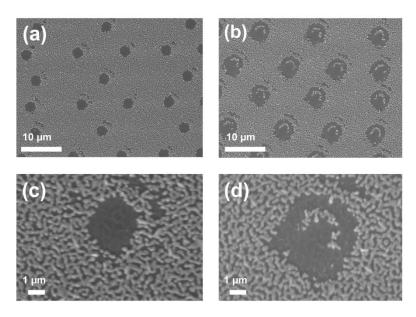
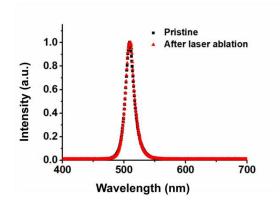
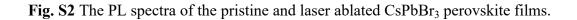


Fig. S1 SEM images and high-magnification SEM images of the microholes fabricated via for FsLRFA patterning technique.





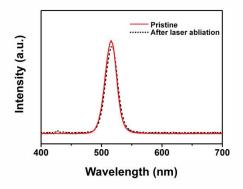


Fig. S3 The PL spectra of the pristine and laser ablated CdSe/ZnS QDs films.

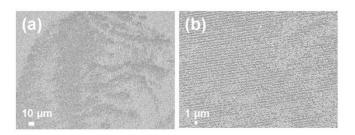


Fig. S4 The SEM images (a) and high-magnification SEM images (b) of the part of cat.

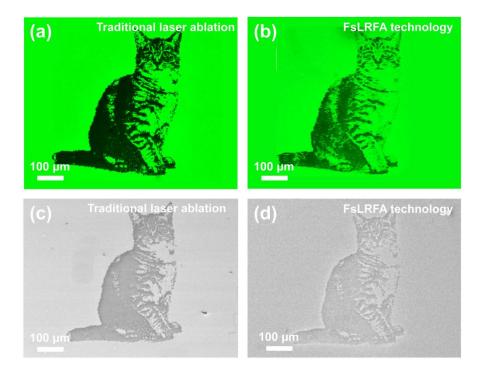


Fig. S5 The fluorescence images (a-b) and SEM images (c-d) of patterned QDs films in traditional laser ablation and FsLRFA process.